



1762

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

September 25, 2003

Applicants : Bruce W. Warnes, et al.  
For : CHEMICAL VAPOR DEPOSITION APPARATUS AND METHOD  
Serial No. : 09/950 013 Group: 1762  
Filed : Sept. 10, 2001 Examiner: Meeks  
Confirmation No. 9221

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

## RESPONSE TO OFFICE ACTION

Dear Sir:

Please amend the above application as follows:

IN THE CLAIMS

1-18. (Canceled)

19. (Currently amended) A method of chemical vapor deposition, comprising flowing coating gas ~~into~~ in a preheat conduit disposed in and along a length of a heated coating chamber ~~along a length thereof~~, heating said coating gas as it flows through said preheat conduit, ~~and~~ discharging the preheated coating gas into a gas distribution conduit in said coating chamber, and discharging the coating gas from the gas distribution conduit through a plurality of gas discharge openings at an opposing manifold wall having a plurality of gas flow openings out of alignment with said gas discharge openings such that there is no line-of-sight gas flow path from said gas distributon openings to said gas flow openings.

20. (Original) The method of claim 19 including heating said coating chamber by disposing it in a heated retort.

21. (Currently amended) The method of claim 19 including discharging the preheated coating gas at a lower end of said preheat conduit to the gas distribution conduit.

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